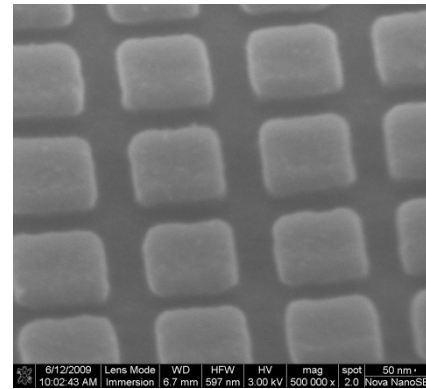
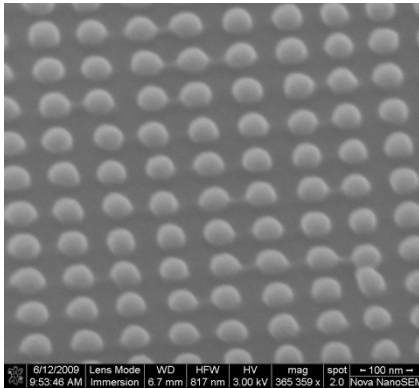


E-beam Lithography with NPGS on the FEI 430 NanoSem



Download the Manual:

<http://ncnc.engineering.ucdavis.edu/pages/equipment/index.html>

FEI 430 NanoSem Electron Beam Lithography System

- [FEI 430 NanoSEM Policy](#)
- [FEI 430 NanoSEM Operating Procedure](#)

Our training procedure is as follows:

SEM Training (1-2 weeks)

- Hands on demonstration after reading Operating Procedure (1hr, free)
- Qualification session, (2 hrs depending on competence, recharge fee + staff time)
- Post qualification, "Going Solo" Session (~1hr, recharge fee + staff time)

NPGS Training (2-4 weeks)

- Introduction to EBL, Stigmating and Focusing the Beam, Produce Alignment Pattern (2hrs)
- Additional hands on practice time as needed, usually 2-3, 2hr sessions